

Nb/Cu coatings characterization in HiPIMS with biased substrate and application of a positive pulse

F. Avino¹, S. Calatroni², A. M. Charley¹, D. Fonnesu³, A. Grudiev⁴, P. Naisson⁵, H. Neupert¹, A. T. Perez Fontenla⁶, T. Richard¹, G. Rosaz¹, A. Sublet¹, M. Taborelli¹

¹ CERN, TE/VSC-SCC

² CERN, TE/VSC-VSM

³ CERN, TE/CRG-CI

⁴ CERN, BE/RF-LRF

⁵ CERN, EN/MME-MA

⁶ CERN, EN/MME-MM

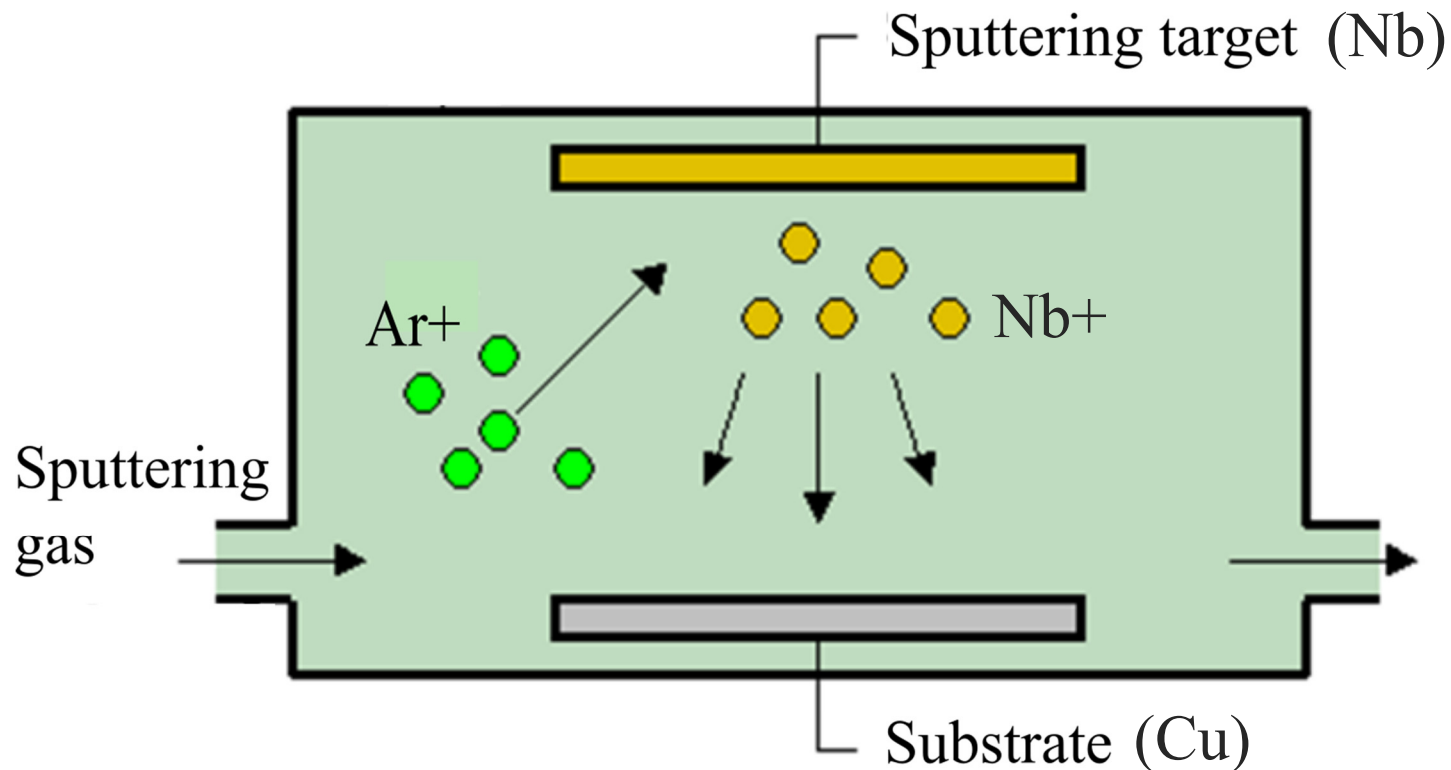
Outline

- Why biased substrate & positive pulse?
- HiPIMS studies with positive pulse
 - Film morphology at grazing angles of incidence
 - Nb/Cu WOW crab cavity R&D
- HiPIMS studies with negatively biased substrate
 - Gas content with sync. biased substrate
 - Residual stress
- Conclusions

Why biased substrate / positive pulse?

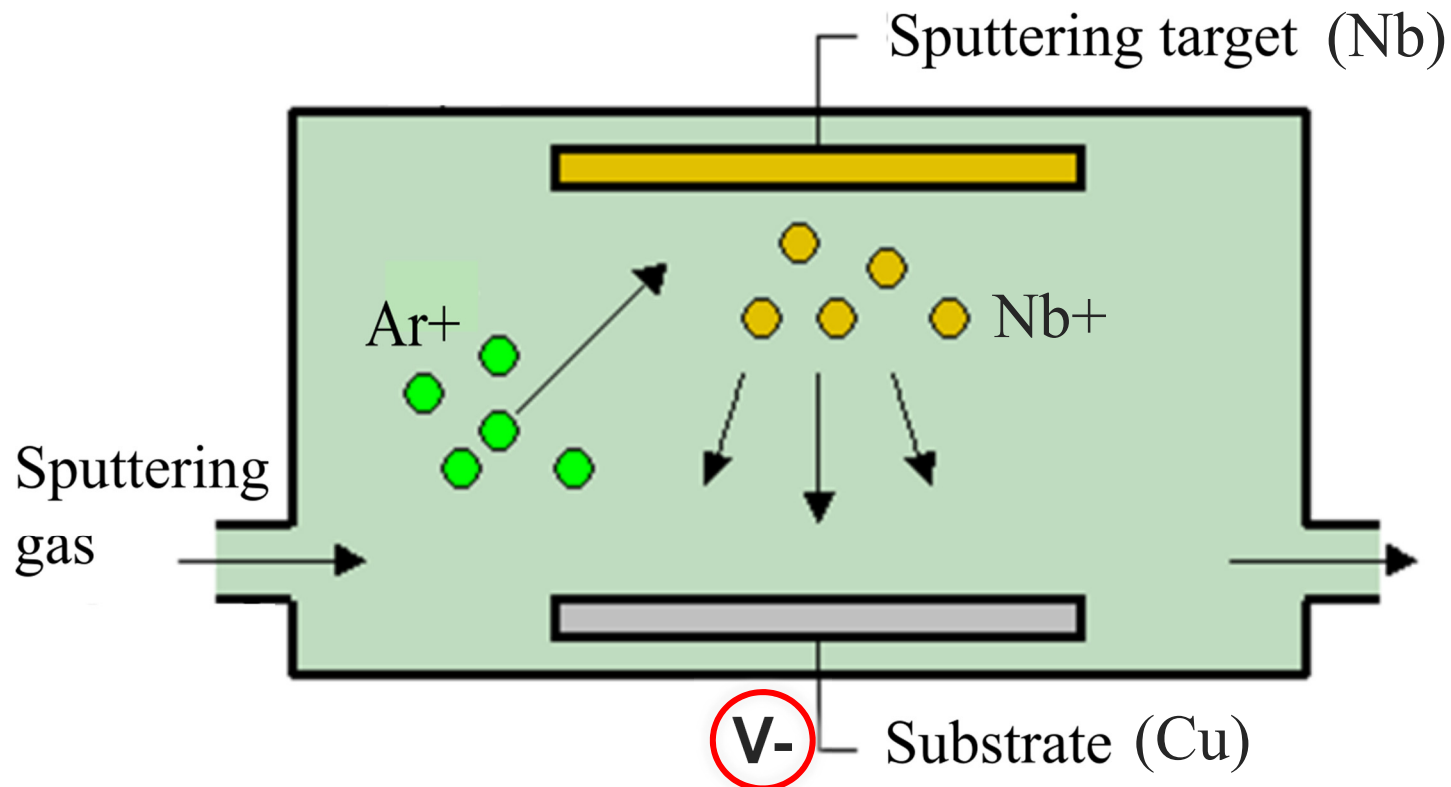
HiPIMS allows to get a higher fraction of metal ions wrt Direct Current Magnetron Sputtering.

How to accelerate the ions towards the substrate?



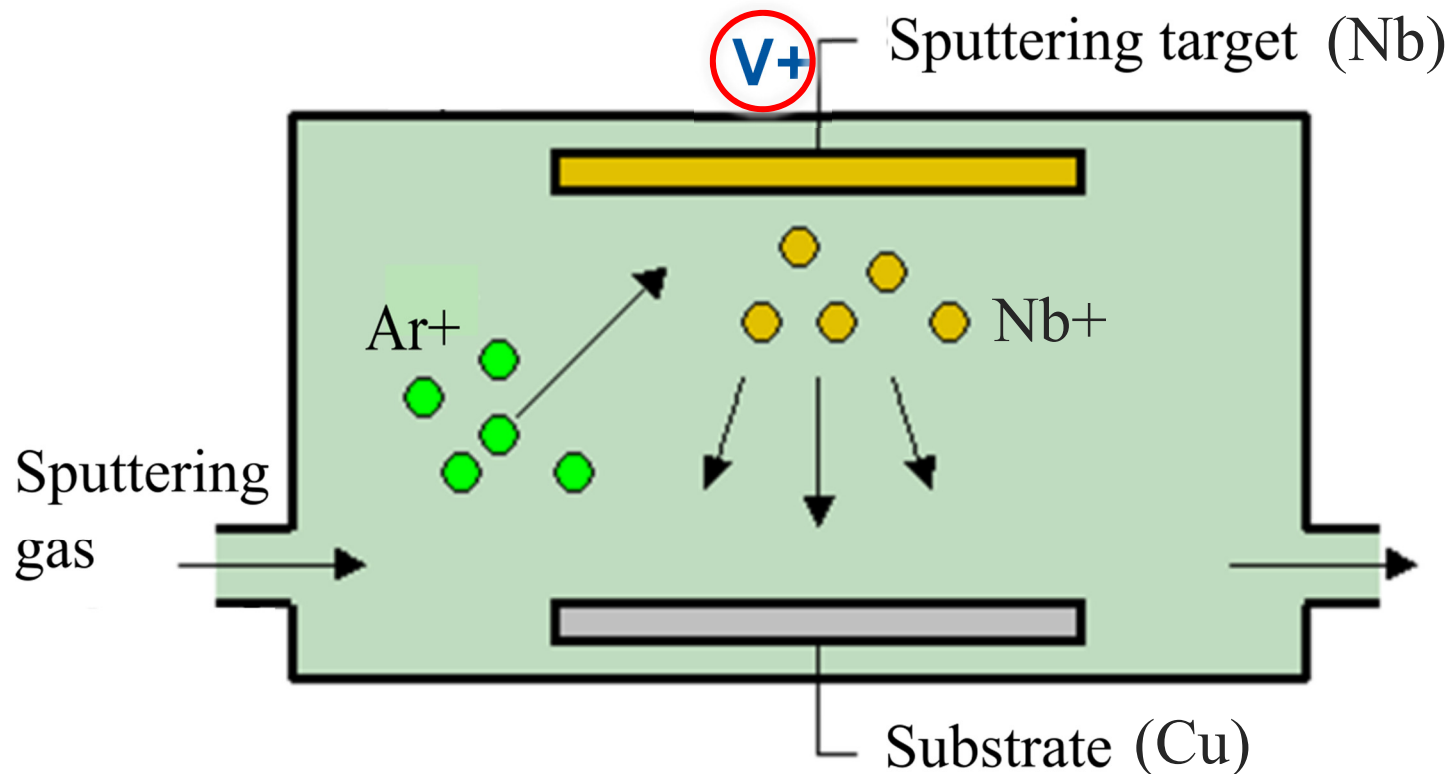
Why biased substrate / positive pulse?

- By negatively biasing the substrate



Why biased substrate / positive pulse?

- By negatively biasing the substrate
- By positive pulse (PP)

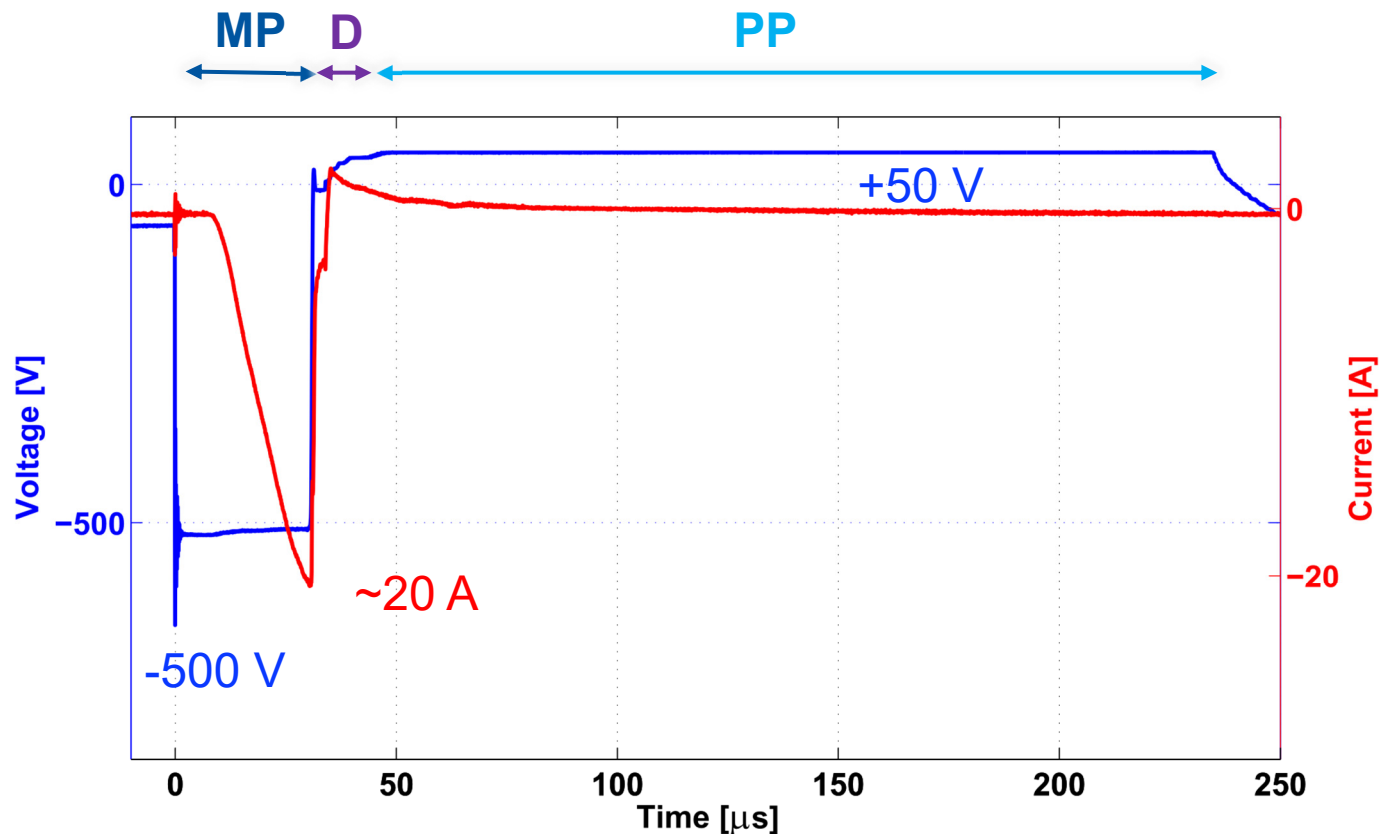


HiPIMS configuration with PP

- Duty cycle : 1 kHz
- Main pulse (**MP**) : 30 μs
- Delay (**D**) : 4 μs
- Positive pulse (**PP**) : 200 μs

PP advantages wrt biased substrate:

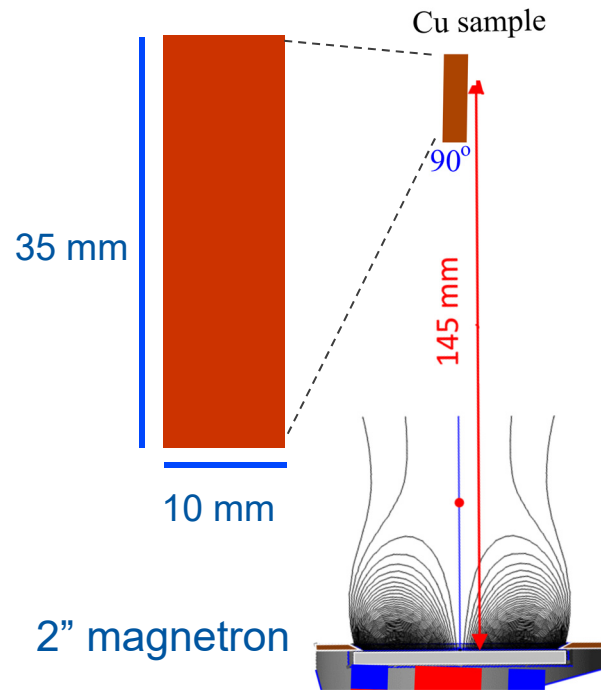
- Simplified magnetron design
- Grounded substrate



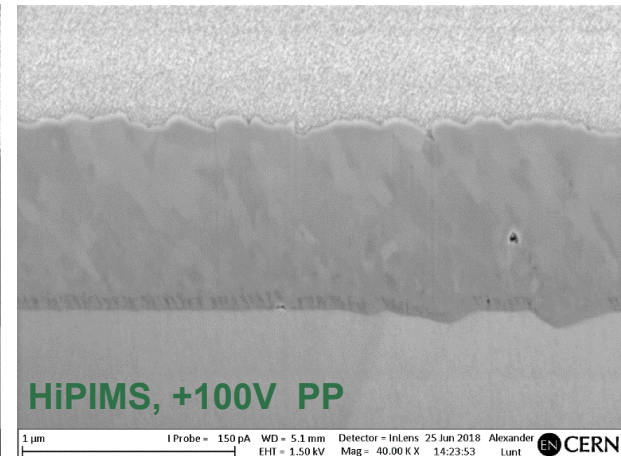
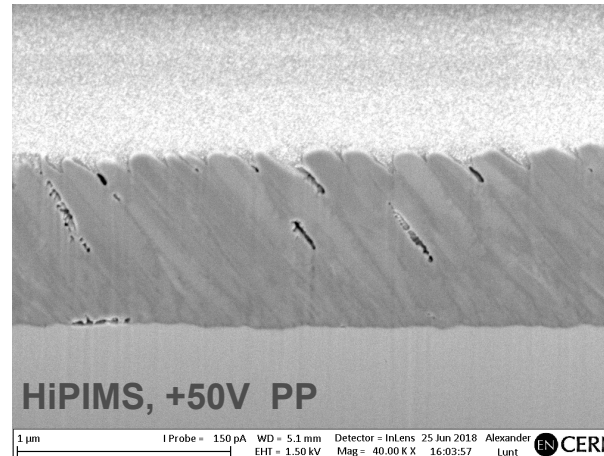
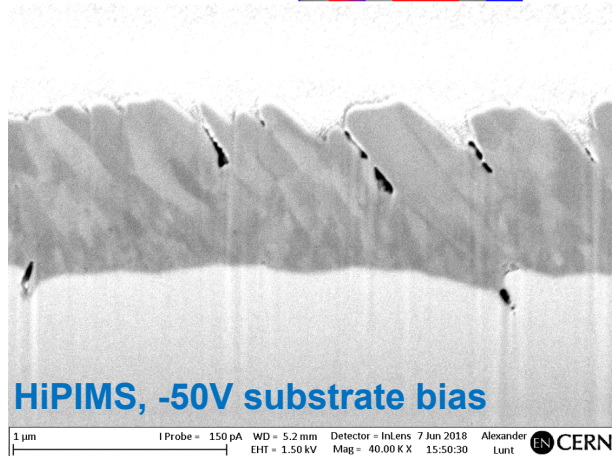
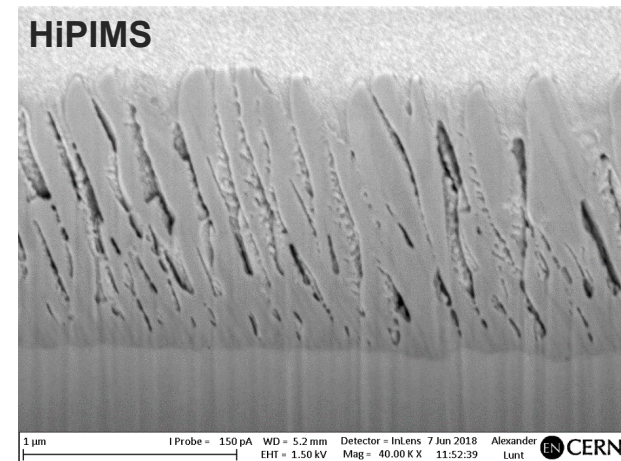
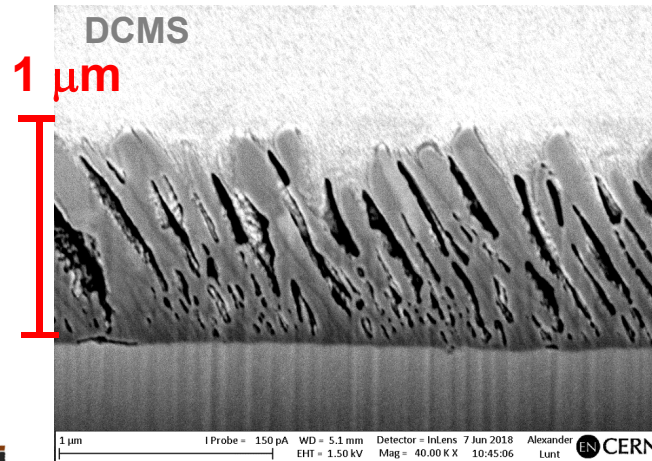
Outline

- Why biased substrate & positive pulse?
- HiPIMS studies with positive pulse
 - Film morphology at grazing angles of incidence
 - Nb/Cu WOW crab cavity R&D
- HiPIMS studies with negatively biased substrate
 - Gas content with sync. biased substrate
 - Residual stress
- Conclusions

FIB / Tc for samples at 90°



Ar pressure : 8×10^{-3} mbar



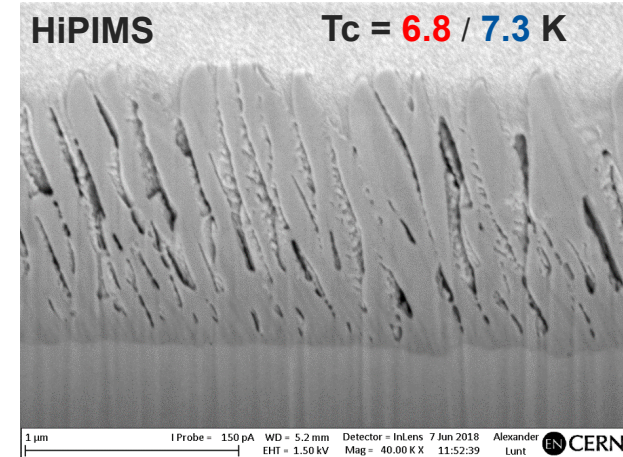
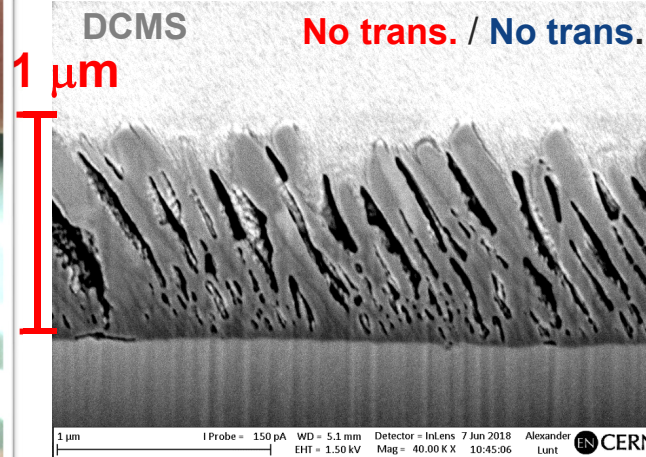
Films coated in HiPIMS + PP similar to HiPIMS + substrate bias!

FIB / Tc for samples at 90°

Coils / SQUID

Fonnesu et al. TUP071

Ar pressure : 8×10^{-3} mbar



Tc = 8.6 / 8.9 K

HiPIMS, -50V substrate bias

1 μm I Probe = 150 pA WD = 5.2 mm Detector = InLens 7 Jun 2018 Alexander Lunt CERN
EHT = 1.50 kV Mag = 40.00 K X 15:50:30

Tc = - / 8.3 K

HiPIMS, +50V PP

1 μm I Probe = 150 pA WD = 5.1 mm Detector = InLens 25 Jun 2018 Alexander Lunt CERN
EHT = 1.50 kV Mag = 40.00 K X 16:03:57

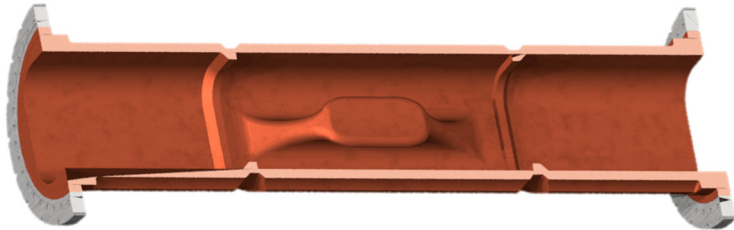
Tc = 8.7 / 9.0 K

HiPIMS, +100V PP

1 μm I Probe = 150 pA WD = 5.1 mm Detector = InLens 25 Jun 2018 Alexander Lunt CERN
EHT = 1.50 kV Mag = 40.00 K X 14:23:53

Films coated in HiPIMS + PP similar to HiPIMS + substrate bias!

Nb/Cu Wide Open Waveguide crab cavity R&D



1st prototype in bulk Cu

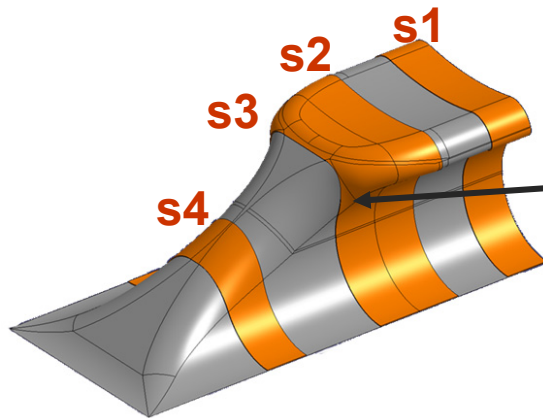
290kg



1.4m

Naisson et al. MOP061

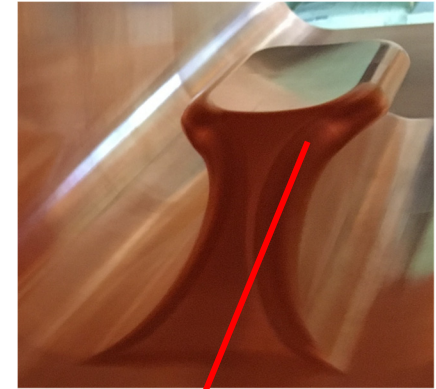
Mockup of 4 sections for coating R&D



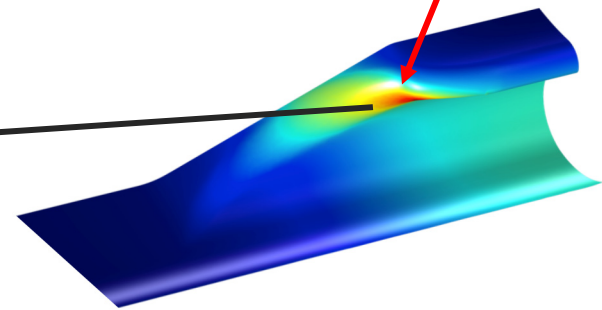
Front view



Detail of tapering



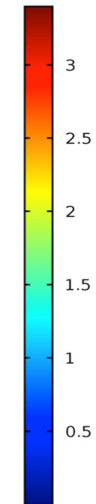
Critical location of highest peak dissipated power



Total power loss ~ 60W
@ $Q_0 = 4 \times 10^8$ / 3 MV deflection

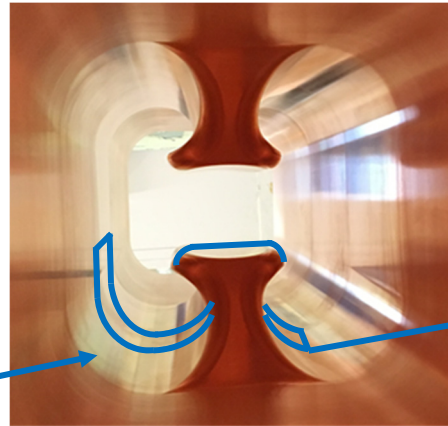
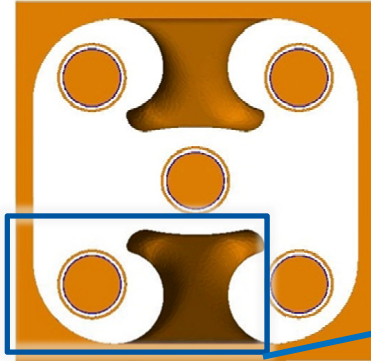
Dissipated P_{surf} [W/m²]

$\times 10^3$

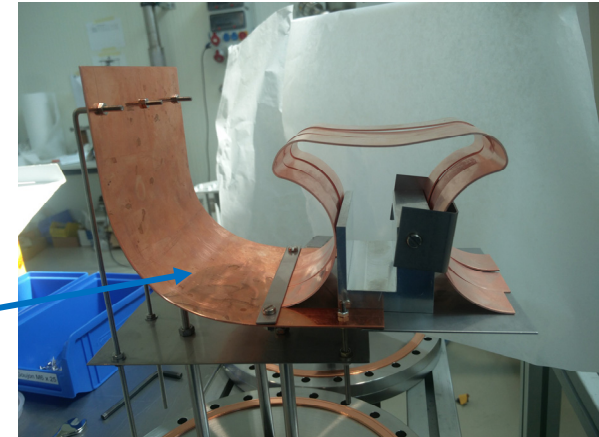


First results on WOW crab cavity samples

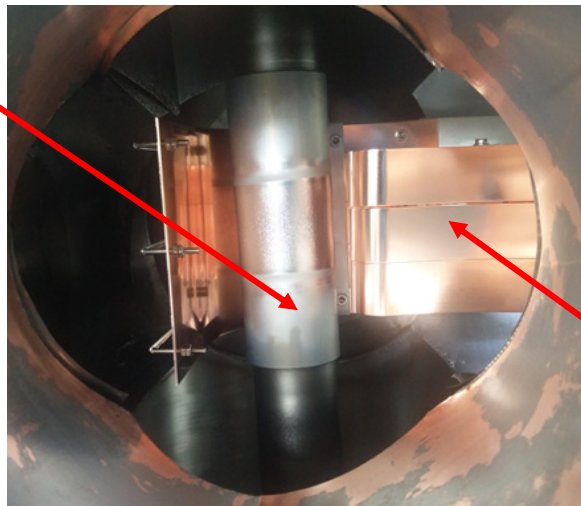
Cathode positions
under investigation



s1 sample: $\frac{1}{4}$ of cavity



Cathode



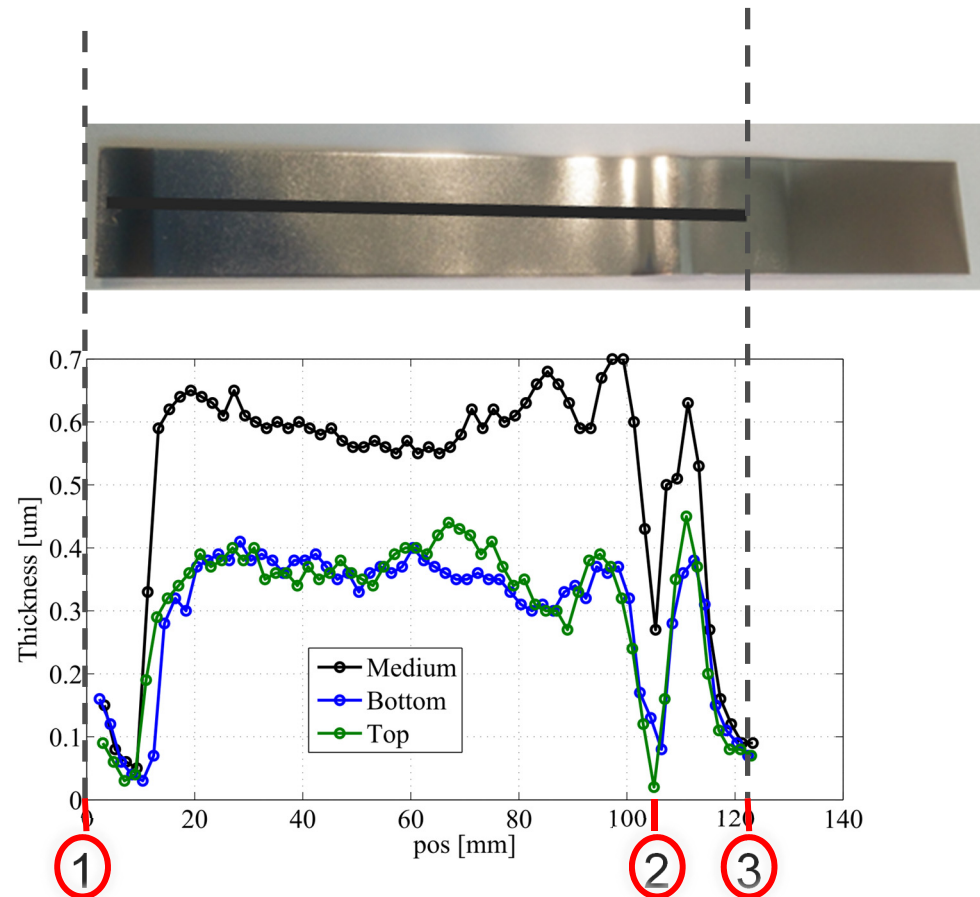
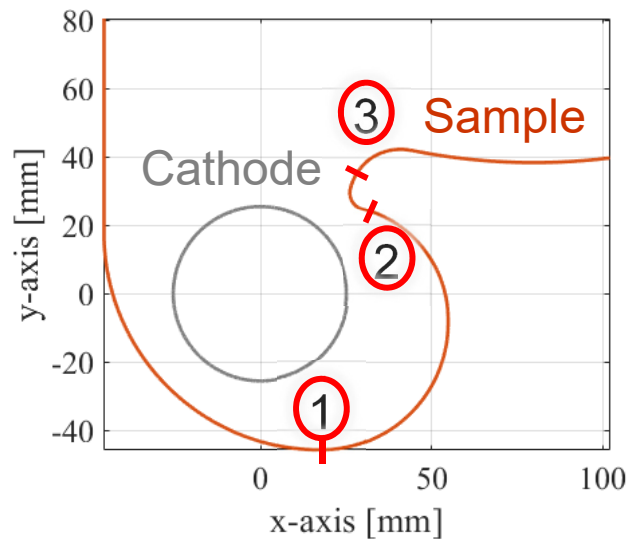
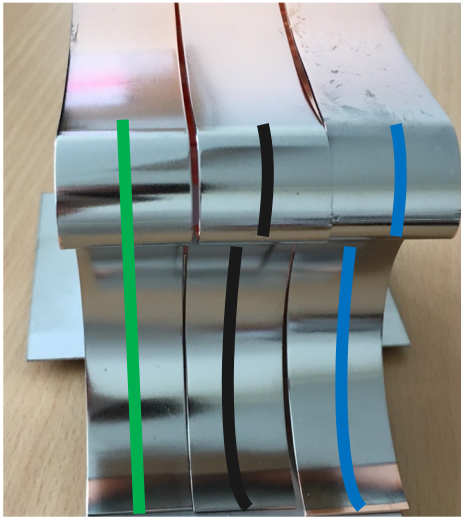
Sample

Assembly in coating chamber



Samples after coating
HiPIMS+PP
1kW, 6 minutes coating,

XRF thickness profiles along sample length

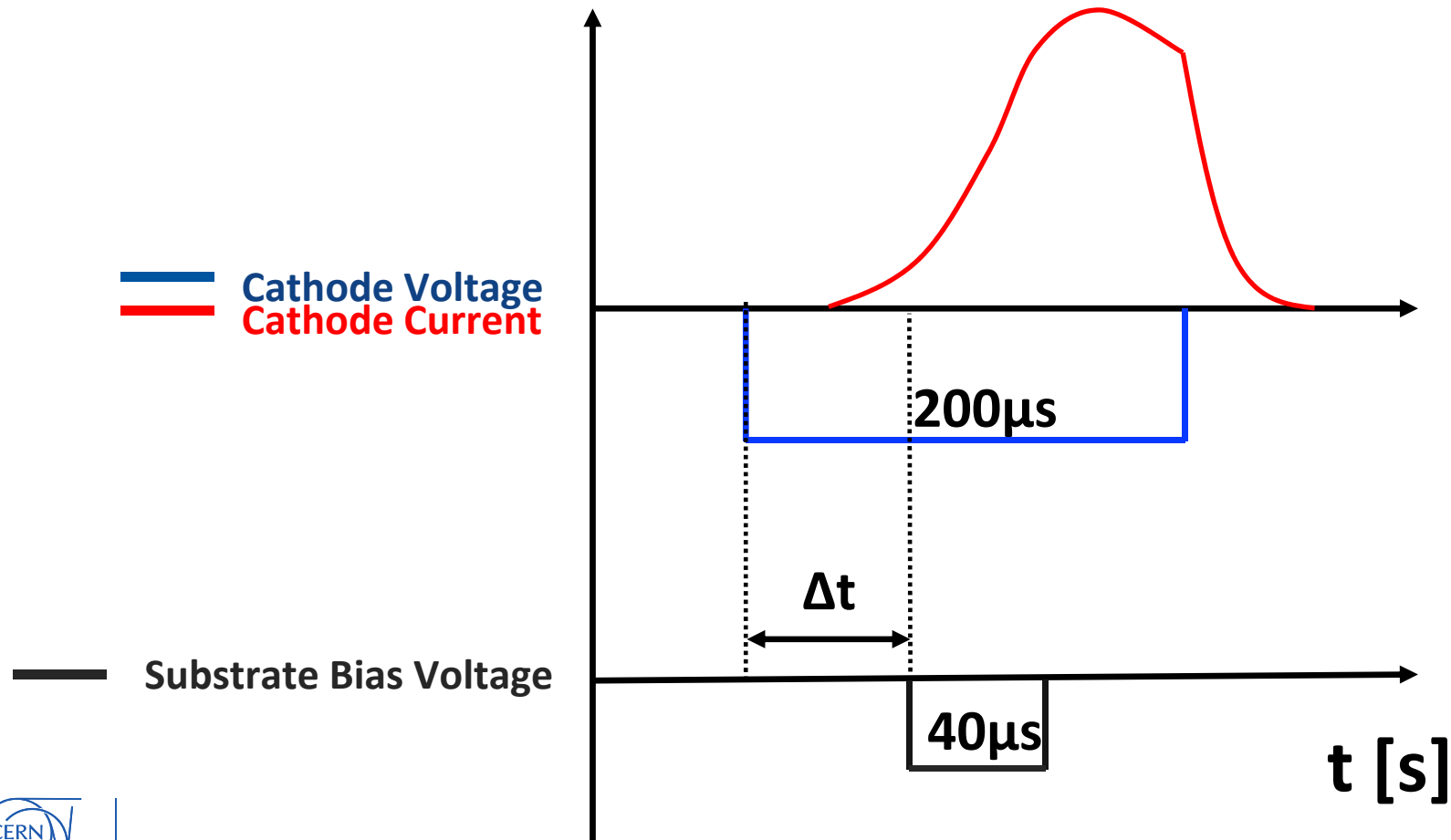


Outline

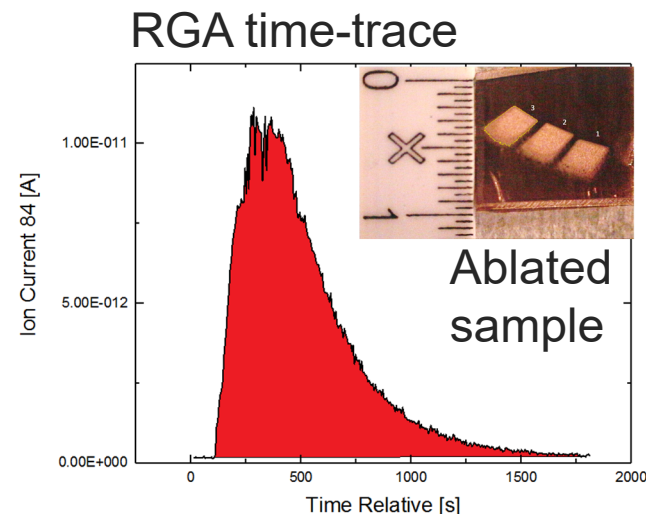
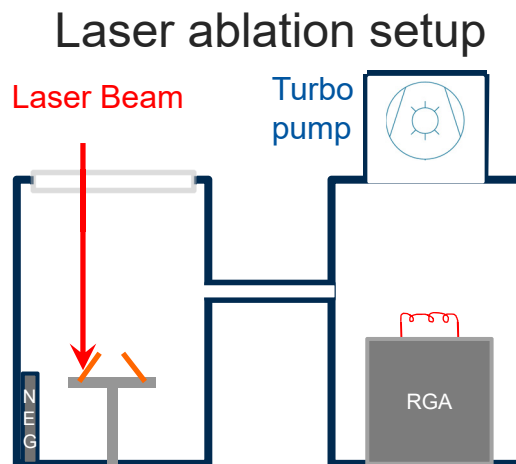
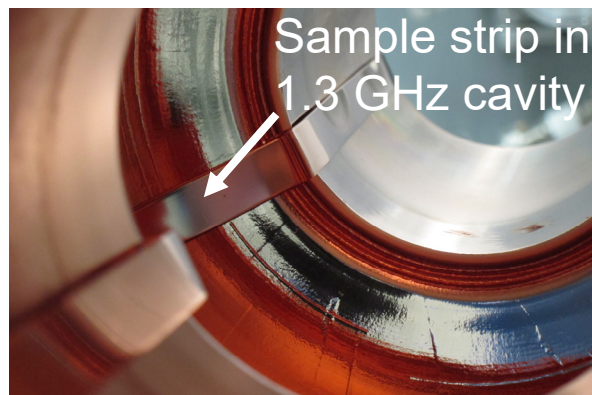
- Why biased substrate & positive pulse?
- HiPIMS studies with positive pulse
 - Film morphology at grazing angles of incidence
 - Nb/Cu WOW crab cavity R&D
- HiPIMS studies with negatively biased substrate
 - Gas content with sync. biased substrate
 - Residual stress
- Conclusions

HiPIMS configuration with sync. biased substrate

By accelerating metal ions, gas ions are accelerated too.
How is the gas content varying by changing the triggering of the substrate bias?

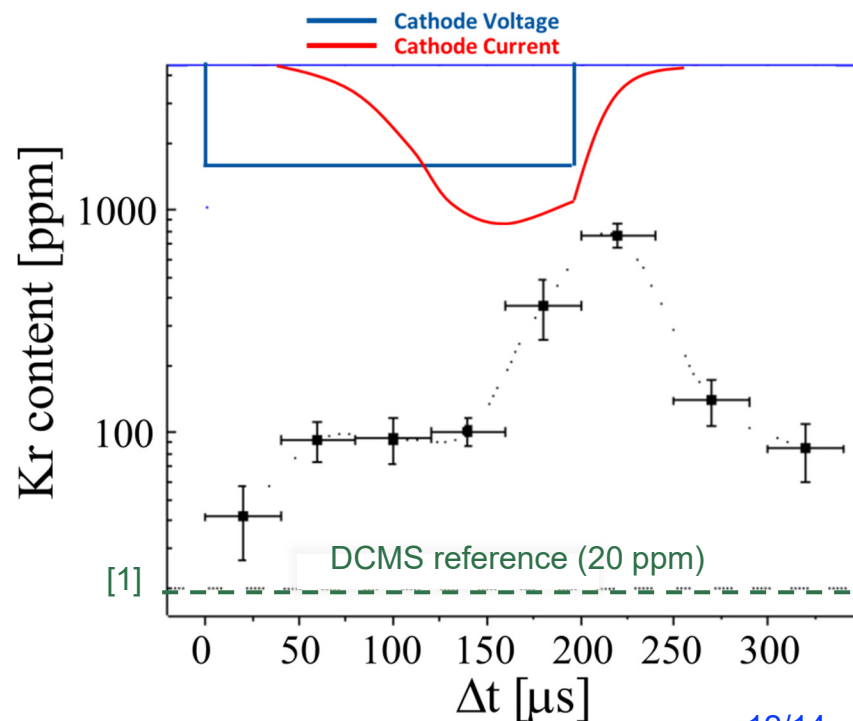


Gas content with sync. biased



Conclusions:

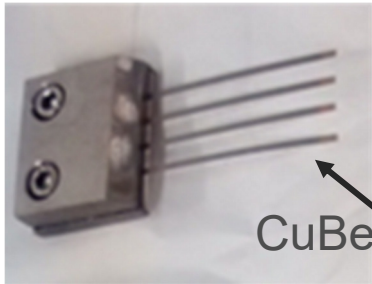
- Gas content can be « tuned » : variations within main pulse up to x22
- Impact on RF performances?



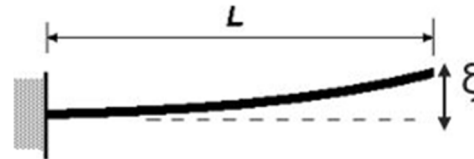
[1] AMOROSI, S., ANDERLE, Mariano, BENVENUTI, C., *et al.* Study of the discharge gas trapping during thin-film growth. *Vacuum*, 2001, vol. 60, no 1-2, p. 89-94.

Residual stress analysis

Is the stress responsible for the frequently observed peel-off in cavities?



CuBe fingers

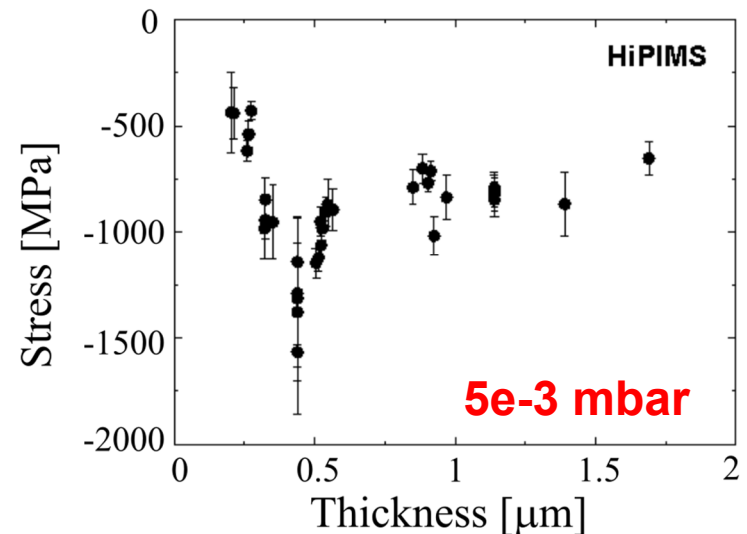
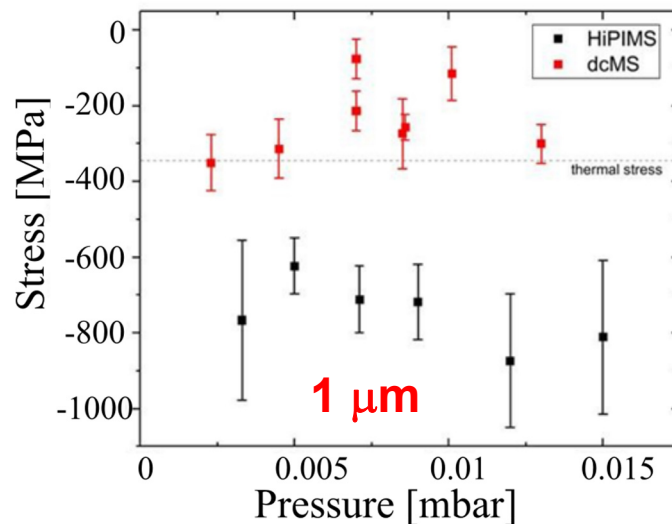


Stoney's equation

$$\sigma = \frac{1}{6} \frac{E_s t_s^2}{(1 - \nu_s) R t_f} ; \quad R = \frac{L^2}{2\xi}$$

Young's modulus

Poisson's ratio



Conclusions:

Significant higher level of stress (x2) in HiPIMS films for all coating pressures, but NO PEEL-OFF

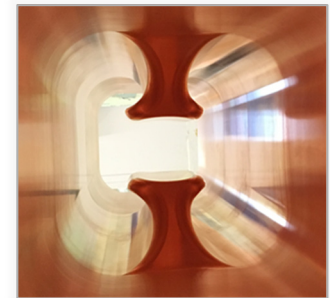
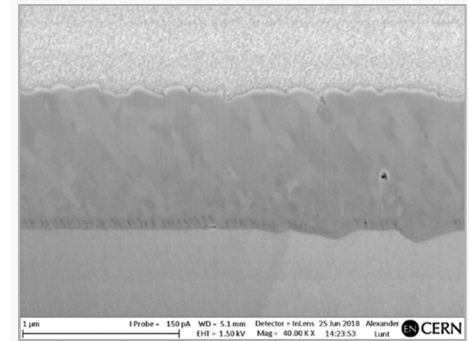
Beyond 500 nm residual stress saturates

Rosaz FRCAB2

Conclusions

HiPIMS + positive pulse (PP):

- Film densification for samples coated at grazing angles (90°) with PP, similarly to biased substrate.
- Preliminary results of films coated on samples with WOW crab cavity inner shape.



HiPIMS + biased substrate:

- High Kr content in film with HiPIMS+biased substrate, but it can be tuned.
- Higher level of stress (up to x2) in HiPIMS films wrt DCMS for all coating pressures, but no peel-off.

